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(54) Title: POLYMER, SEMICONDUCTOR COMPOSITION COMPRISING POLYMER, AND METHOD FOR MANUFACTURING FILM USING SEMICONDUCTOR COMPOSITION

(57) Abstract: To provide a novel polymer capable of reducing sublimate during film formation and a composition comprising the same. The polymer (A) according to the present invention comprises at least one structural unit selected from the group consisting of Unit (a), Unit (b), Unit (c) and Unit (d) having certain structures, wherein, n_a , n_b , n_c and n_d , which are the numbers of repetition respectively of Units (a), (b), (c) and (d), satisfy the following formulae: $n_a + n_b > 0$, $n_c \geq 0$ and $n_d \geq 0$.



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